

PATENT ABSTRACTS OF JAPAN

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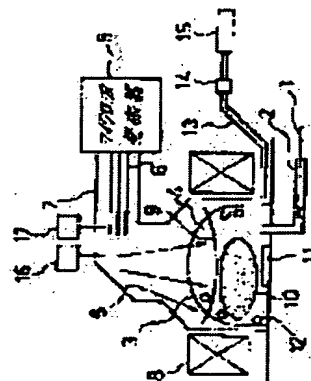
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(54) SEMICONDUCTOR MANUFACTURING EQUIPMENT

(57)Abstract:

PURPOSE: To obtain a semiconductor manufacturing equipment capable of stably judging the end of etching with time independent of the adhesion amount of reaction product to a processing chamber and the fluctuation of light emitted from plasma in an unequilibrium state when a film is etched by using a microwave ECR etcher.

CONSTITUTION: A measuring means 16 of microwave incidence power into a processing chamber 4 and a measuring means 17 of microwave reflection power on an ECR surface 9 are provided. The power intensity of microwave reflected by the ECR surface 9 depends upon the kind of a film to be etched. On the basis of this fact, power intensity of the above microwave is monitored during etching, and thereby the end of etching is judged.



LEGAL STATUS

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